

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE

(Rev.2-32) PATENT AND TRADEMARK OFFICE
INFORMATION DISCLOSURE
STATEMENT BY APPLICANT
(Use several sheets if necessary)

Atty Docket: ADACHI P163USP2
Examiner: John J. Hoffmann
Group: 1731
Applicant: Akira IKUSHIMA, Kazuya SAITO, Takashi
MIURA and Shogo NASUDA

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Sub-Class	Class	Filing Date, if Appropriate
	4,028,080	Jun. 1977	Di Vita	—	—	
	4,157,253	Jun. 1979	Hemphill	—	—	
	4,182,664	Jan. 1980	Maklad	—	—	
	5,267,343	Nov. 1993	Lyons	—	—	
	5,620,496	Apr. 1997	Erdoqan	—	—	
	5,983,673	Nov. 1999	Urano	—	—	
	6,056,739	May 2000	Morton	—	—	
	5,478,371	Dec. 26, 1995	Lemaire et al	—	—	

FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Country	Sub-Class	Class	Translation Yes No
	0 687 924 A1	Dec. 20, 1995	EPO	—	—	
	2808457	Aug. 1974	Germany	—	—	
	4-342427		Japan	—	—	
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	6-199539	Jun. 7, 1994	Japan	—	—	
	52-94657	Nov. 1993	Japan	—	—	
	54-134721	Oct. 1979	Japan	—	—	
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	61-45201	Mar. 5, 1986	Japan	—	—	
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

"Thermal Annealing of Defects Induced by ArF Excimer Laser Irradiation in a SiO₂"; Japanese Society of Applied Physics, Catalog No. AP 90110-02 (English Translation)

ROTHSCHILD, Mordechai, Daniel J. EHRLICH and David C. SHAVER, "Excimer Laser Induced Damage in Fused Silica", *Microelectronic Engineering* 11, 1990, pp. 167-172.

"Temperature Dependence of the E⁺ Center Creation in Silica Glasses", *Physica Status Solidi (b)*, vol. 147, No. 1, 1988, pp.k1-k4.

J Hoff

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in Parent

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